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AMENDMENT TRANSMITTAL LETTER

Docket No.
SON-2920

Application No.
10/780,667-Conf. #1986

Filing Date
February 19, 2004

Examiner
Not Yet Assigned

Art Unit
1756

Applicant(s): Ichiro HASE

Invention: EXPOSURE PATTERN OR MASK AND INSPECTION METHOD AND MANUFACTURE
METHOD FOR THE SAME

TO THE COMMISSIONER FOR PATENTS

Transmitted herewith is an amendment in the above-identified application.

The fee has been calculated and is transmitted as shown below.

CLAIMS AS AMENDED					
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate	
Total Claims	23	- 23 =		x	
Independent Claims	3	- 3 =		x	
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>					
Other fee (please specify):					
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:					0.00

☒ Large Entity

☐ Small Entity

☒ No additional fee is required for this amendment.

☐ Please charge Deposit Account No. _____ in the amount of \$ _____.
A duplicate copy of this sheet is enclosed.

☐ A check in the amount of \$ _____ to cover the filing fee is enclosed.

☐ Payment by credit card. Form PTO-2038 is attached.

☒ The Director is hereby authorized to charge and credit Deposit Account No. 18-0013
as described below. A duplicate copy of this sheet is enclosed.

☒ Credit any overpayment.

☒ Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.

Dated: November 1, 2004

Ronald P. Kananen
Attorney Reg. No.: 24,104

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Docket No.: SON-2920
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hironori IBUSUKI

Confirmation No.: 1986

Application No.: 10/780,667

Art Unit: 1756

Filed: February 19, 2004

Examiner: Not Yet Assigned

For: EXPOSURE PATTERN OR MASK AND
INSPECTION METHOD AND
MANUFACTURE METHOD FOR THE SAME

FIRST PRELIMINARY AMENDMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination on the merits, please amend the above-identified U.S. patent application as follows: